




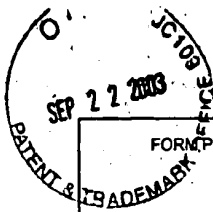
FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMEX.284C1	APPLICATION NO. 10/826,212
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		
APPLICANT Pomareda, et al.		
FILING DATE July 24, 2003		GROUP Unknown 2823

(USE SEVERAL SHEETS IF NECESSARY)

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
Lee	1	2,394,930	2/12/46	McRae			
	2	3,895,127	7/15/75	Comizzoli			
	3	4,056,642	11/1/77	Saxena et al.			
	4	4,292,343	9/29/81	Plaettner et al.			
	5	4,343,830	8/10/82	Sarma et al.			
	6	4,436,761	3/13/84	Hayashi et al.			
	7	4,544,571	10/1/85	Miller			
	8	4,645,683	2/24/87	Gourrier et al.			
	9	4,766,006	8/23/88	Gaczi			
	10	5,135,775	8/4/92	Foller et al.			
	11	5,281,546	01/25/94	Possin et al.			
	12	5,576,071	11/19/96	Sandhu			
	13	5,587,205	12/24/96	Saito et al.			
	14	5,780,115	7/14/98	Park et al.			
	15	5,939,763	08/17/99	Hao et al.			
	16	5,950,107	09/07/99	Huff et al.			
	17	5,990,013	11/23/99	Berenguer et al.			
	18	5,993,916	11/30/99	Zhao et al.			
	19	6,107,192	08/22/00	Subrahmanyam et al.			
Lee	20	6,200,866	03/13/01	Ma et al.			

FOREIGN PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	21	JP 60 254621 A	16.12.85	Patent Abstracts of Japan				
	22	JP 2000 160342 A	13.10.00	Patent Abstracts of Japan				
	23	0 617 461 A2	03/16/94	EPO				

EXAMINER Brian May Lee	DATE CONSIDERED 5/27/2004
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	



FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMEX.284C1	APPLICATION NO. 10/626,212
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY)	APPLICANT Pomareda, et al.	
	FILING DATE July 24, 2003	GROUP Unknown 2823

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
<i>Re</i>	24 Kim, H. and R. Reif, <i>Thin Solid Films</i> , Vol. 289:192-198 (1996), "In-situ low-temperature (600°C) wafer surface cleaning by electron cyclotron resonance hydrogen plasma"
<i>Lu</i>	25 Ramm J. and E. Beck, <i>Thin Solid Films</i> , Vol. 246:158-163 (1994), "Low temperature epitaxial growth by molecular beam epitaxy on hydrogen-plasma-cleaned silicon wafers."

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EXAMINER <i>Kevin Ming Lee</i>	DATE CONSIDERED <i>5/27/2004</i>
*EXAMINER: INITIAL IF CITATION CONSIDERED. WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED. INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	